SENTECH Erfolg durch Leistung

Berlin, 9/17/2019

Aktuelles Experiment:
noname.rcp

Modellbeschreibung

Number	Layer Name	Thickness [nm]	Refr. Index [632.8 nm]	Fitted
0	Air	-	1.000	no
1	NoName0	0.50	3.010	yes
2	Silicon DUV-NIR	-	3.874	no

Fit parameter

Fit parameter	Fit result
[1,1] NoName0: Thickness [nm]	0.50

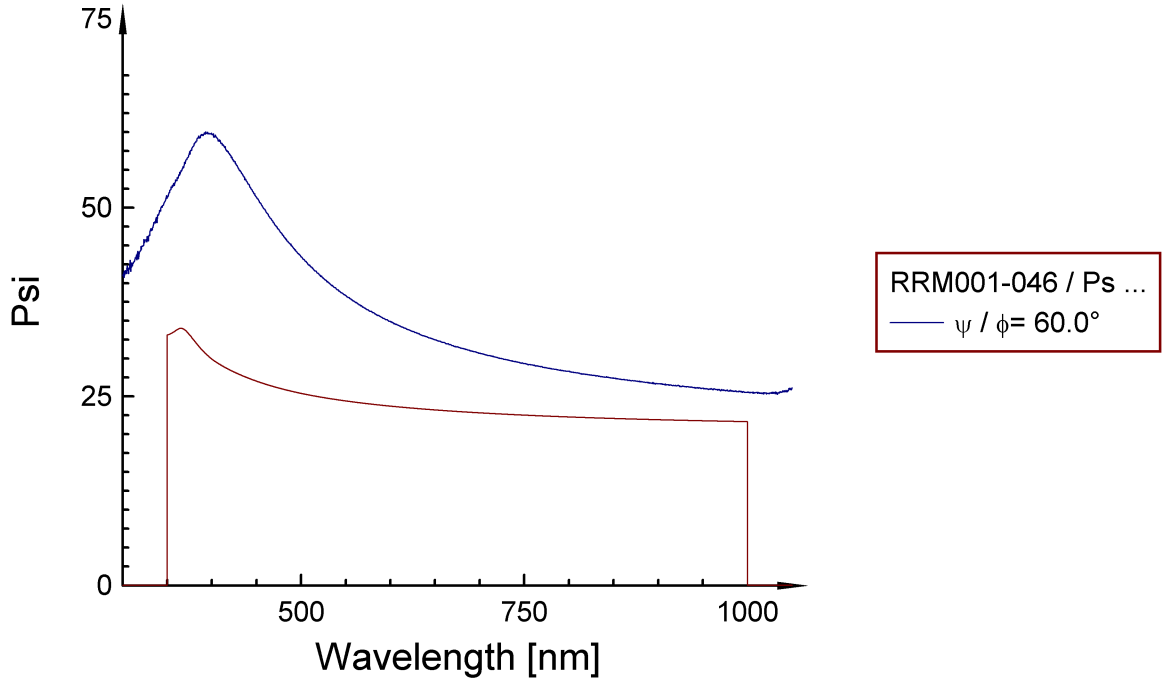
All parameter

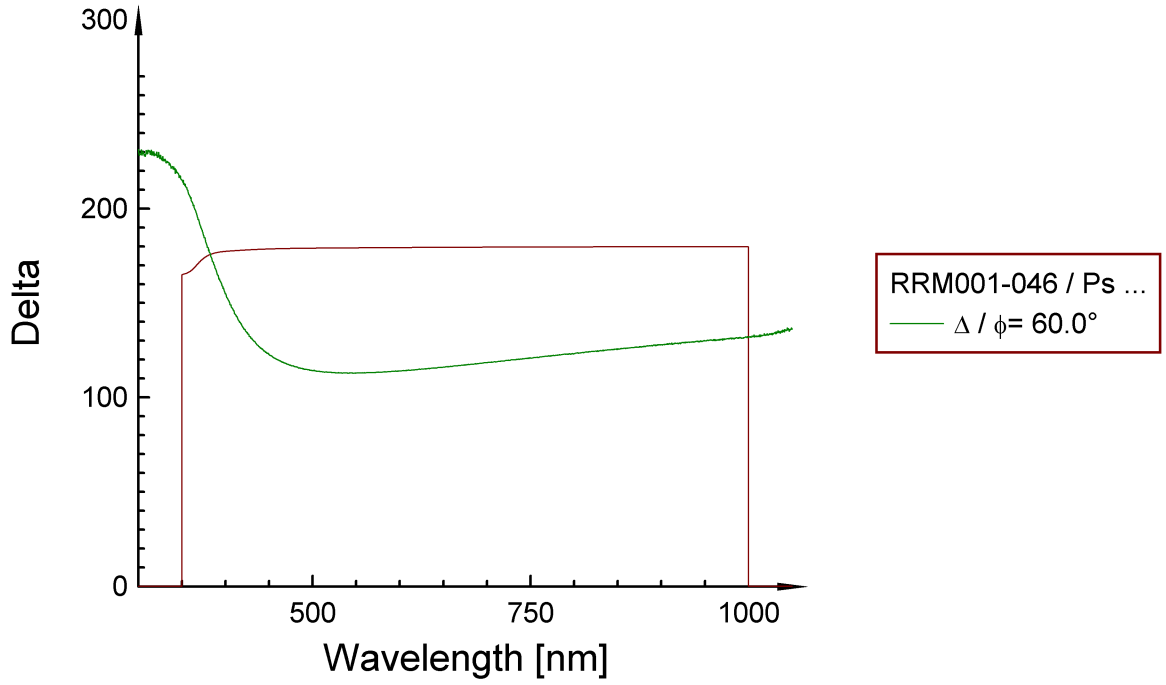
Parameter	Value
[1] Wavelength [nm]	632.8
[1] Angle [°]	70.00
[1] Time [s]	0.0
[1] Temperature [°C]	23.5
[1] Sample rotation [°]	0.00
[1] Depol. D0	1.0000
[1] Depol. D1	0.0000
[1] Depol. D2	0.0000
[1] Beam diameter	4.00
[1] Aperture diameter	4.00
[1,1] Thickness variation	10.0
[1] Wavelength resolution (nm)	0.0
[1] Angle variation	3.0
[1] Angle offset [°]	0.00
[1] Wavelength Offset (nm)	0.00
[1] Wavelength Linear	1.00000
[1] Fraction Overlayer	1.000
[1] Backside Factor	1.000
Air: Refr. index	1.000
Air: Absorption	0.000
Air: N Offset	0.00000
Air: K Offset	0.00000

[1,1] NoName0: Thickness [nm]	0.50
NoName0: N0	3.000
NoName0: N1	40.0
NoName0: N2	0.0
NoName0: K0	0.000
NoName0: K1	0.000
NoName0: K2	0.000
NoName0: N Offset	0.00000
NoName0: K Offset	0.00000
Silicon DUV-NIR: N Offset	0.00000
Silicon DUV-NIR: K Offset	0.00000
Pola.Pos.	45.00
Pola.Offs.	0.00
Ret.Axis	0.00
Ret.Phase	90.00
Eta	1.00000
Ana.Offs.	0.00
Ana.Offs.Lin.	0.00
Ana.Offs.Quadr.	0.00
Psi Offs.	0.00
Psi Lin.	0.00
Psi Quadr.	0.00
Delta Offs.	0.00
Delta Lin.	0.00
Delta Quadr.	0.00
MSE	44.18462077

Measured Data

RRM001-046 / Psi, Delta / Spectral range: 300.2 nm - 1050.0 nm / Angle of incidence: 60.00 ° / 9/17/2019 4:09:13 PM


75
50
25
0
Psi
500
750
1000
Wavelength [nm]
RRM001-046 / Ps ...
ψ / ϕ= 60.0°


300
200
100
0
Delta
500
750
1000
Wavelength [nm]
RRM001-046 / Ps ...
Δ / ϕ= 60.0°